

L Number	Hits	Search Text	DB	Time stamp
1	2	("6723632").PN.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/10/14 07:40
44	6677	((critical near3 dimension) or (line near3 width) or (distance near5 line)) with range	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/10/14 09:24
45	9474	((photoresist adj mask) or (photo adj mask) or mask or reticle) and (parasitic near4 capacitance)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/10/14 11:27
46	64	((critical near3 dimension) or (line near3 width) or (distance near5 line)) with range ) and ((photoresist adj mask) or (photo adj mask) or mask or reticle) and (parasitic near4 capacitance))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/10/14 08:16
47	7833	716/\$.ccls.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/10/14 08:17
48	1	((critical near3 dimension) or (line near3 width) or (distance near5 line)) with range ) and ((photoresist adj mask) or (photo adj mask) or mask or reticle) and (parasitic near4 capacitance))) and 716/\$.ccls.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/10/14 09:20
49	22	penetration and 716/\$.ccls.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/10/14 09:21
50	11	((critical near3 dimension) or (line near3 width) or (distance near5 line)) and (penetration and 716/\$.ccls.)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/10/14 09:34
51	6	((photoresist adj mask) or (photo adj mask) or mask or reticle) and ((critical near3 dimension) or (line near3 width) or (distance near5 line)) and (penetration and 716/\$.ccls.))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/10/14 09:33
52	0	((photoresist adj mask) or (photo adj mask) or mask or reticle) and ((critical near3 dimension) or (line near3 width) or (distance near5 line)) and (penetration and 716/\$.ccls.))) and (parasitic near4 capacitance)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/10/14 09:31
53	2507	penetrat\$3 and (parasitic near4 capacitance)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/10/14 10:09
54	1737	((photoresist adj mask) or (photo adj mask) or photolithograph\$5 or mask or reticle) and (penetrat\$3 and (parasitic near4 capacitance))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/10/14 10:20
55	432	((critical near3 dimension) or (line near3 width) or (distance near5 line)) and ((photoresist adj mask) or (photo adj mask) or photolithograph\$5 or mask or reticle) and (penetrat\$3 and (parasitic near4 capacitance)))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/10/14 11:29
56	1	((critical near3 dimension) or (line near3 width) or (distance near5 line)) and ((photoresist adj mask) or (photo adj mask) or photolithograph\$5 or mask or reticle) and (penetrat\$3 and (parasitic near4 capacitance))) and 716/\$.ccls.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/10/14 09:36
59	4	((penetrat\$3 or insert\$3 or interven\$3 or mediat\$3 or interpos\$3) same (inter adj line)) and (parasitic near4 capacitance)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/10/14 10:13

60	28	(penetrat\$3 or insert\$3 or interven\$3 or mediat\$3 or interpos\$3) and (inter adj line) and (parasitic near4 capacitance)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/10/14 11:25
61	21	((critical near4 dimension) or (line near4 width) or (distance near5 line) or (line near4 dimension)) and ((penetrat\$3 or insert\$3 or interven\$3 or mediat\$3 or interpos\$3) and (inter adj line) and (parasitic near4 capacitance))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/10/14 10:15
62	0	716/\$.ccls. and (((critical near4 dimension) or (line near4 width) or (distance near5 line) or (line near4 dimension)) and ((penetrat\$3 or insert\$3 or interven\$3 or mediat\$3 or interpos\$3) and (inter adj line) and (parasitic near4 capacitance)))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/10/14 10:16
63	20	(simulat\$3 or design\$3 or model\$4) and (((critical near4 dimension) or (line near4 width) or (distance near5 line) or (line near4 dimension)) and ((penetrat\$3 or insert\$3 or interven\$3 or mediat\$3 or interpos\$3) and (inter adj line) and (parasitic near4 capacitance)))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/10/14 12:56
64	6	simulat\$3 and (((critical near4 dimension) or (line near4 width) or (distance near5 line) or (line near4 dimension)) and ((penetrat\$3 or insert\$3 or interven\$3 or mediat\$3 or interpos\$3) and (inter adj line) and (parasitic near4 capacitance)))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/10/14 10:17
65	12	((photoresist adj mask) or (photo adj mask) or photolithograph\$5 or mask or reticle) and ((simulat\$3 or design\$3 or model\$4) and (((critical near4 dimension) or (line near4 width) or (distance near5 line) or (line near4 dimension)) and ((penetrat\$3 or insert\$3 or interven\$3 or mediat\$3 or interpos\$3) and (inter adj line) and (parasitic near4 capacitance))))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/10/14 10:20
66	12107	(penetrat\$3 or insert\$3 or interven\$3 or mediat\$3 or interpos\$3 or shield\$3) and (parasitic near4 capacitance)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/10/14 13:10
67	5362	((photoresist adj mask) or (photo adj mask) or mask or reticle or photolithograph\$5) and ((penetrat\$3 or insert\$3 or interven\$3 or mediat\$3 or interpos\$3 or shield\$3) and (parasitic near4 capacitance))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/10/14 11:29
68	76	((photoresist adj mask) or (photo adj mask) or mask or reticle or photolithograph\$5) and ((penetrat\$3 or insert\$3 or interven\$3 or mediat\$3 or interpos\$3 or shield\$3) and (parasitic near4 capacitance))) and 716/\$.ccls.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/10/14 11:29
69	14	((critical near3 dimension) or (line near3 width) or (distance near5 line)) and (((photoresist adj mask) or (photo adj mask) or mask or reticle or photolithograph\$5) and ((penetrat\$3 or insert\$3 or interven\$3 or mediat\$3 or interpos\$3 or shield\$3) and (parasitic near4 capacitance))) and 716/\$.ccls.)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/10/14 12:55
70	13	"5136358"	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/10/14 12:54

71	3	((penetrat\$3 or insert\$3 or interven\$3 or mediat\$3 or interpos\$3 or shield\$3) and (parasitic near4 capacitance)) and "5136358"	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/10/14 12:55
72	2	((critical near3 dimension) or (line near3 width) or (distance near5 line)) and ((penetrat\$3 or insert\$3 or interven\$3 or mediat\$3 or interpos\$3 or shield\$3) and (parasitic near4 capacitance)) and "5136358")	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/10/14 13:09
73	2	(simulat\$3 or design\$3 or model\$4) and (((critical near3 dimension) or (line near3 width) or (distance near5 line)) and ((penetrat\$3 or insert\$3 or interven\$3 or mediat\$3 or interpos\$3 or shield\$3) and (parasitic near4 capacitance)) and "5136358"))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/10/14 13:06
74	24	((("5808366") or ("5796986") or ("5761080") or ("5694344") or ("5610833") or ("5500804") or ("5410491") or ("5379231") or ("5236871") or ("4884122") or ("3838442"))).PN.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/10/14 13:06
75	7	716/\$.ccls. and (((("5808366") or ("5796986") or ("5761080") or ("5694344") or ("5610833") or ("5500804") or ("5410491") or ("5379231") or ("5236871") or ("4884122") or ("3838442"))).PN.)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/10/14 13:06
76	3	((critical near3 dimension) or (line near3 width) or (distance near5 line)) and (716/\$.ccls. and (((("5808366") or ("5796986") or ("5761080") or ("5694344") or ("5610833") or ("5500804") or ("5410491") or ("5379231") or ("5236871") or ("4884122") or ("3838442"))).PN.))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/10/14 13:09
77	0	((penetrat\$3 or insert\$3 or interven\$3 or mediat\$3 or interpos\$3 or shield\$3) and (parasitic near4 capacitance)) and (((critical near3 dimension) or (line near3 width) or (distance near5 line)) and (716/\$.ccls. and (((("5808366") or ("5796986") or ("5761080") or ("5694344") or ("5610833") or ("5500804") or ("5410491") or ("5379231") or ("5236871") or ("4884122") or ("3838442"))).PN.)))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/10/14 13:10
78	2	((critical near3 dimension) or (line near3 width) or (distance near5 line)) and (716/\$.ccls. and (((("5808366") or ("5796986") or ("5761080") or ("5694344") or ("5610833") or ("5500804") or ("5410491") or ("5379231") or ("5236871") or ("4884122") or ("3838442"))).PN.))) and (parasitic near4 capacitance)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/10/14 13:10
-	9463	((photoresist adj mask) or (photo adj mask) or mask or reticle) and (parasitic near4 capacitance)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/10/14 08:15
-	13	((critical near3 dimension) with range) and (((photoresist adj mask) or (photo adj mask) or mask or reticle) and (parasitic near4 capacitance))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/10/14 08:12
-	2	("6414367").PN.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/10/13 16:17